

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In Re Application of:

Robert David Allen et al.

Examiner: John S. Y. Chu

Serial No.: 10/729,452

Group Art Unit: 1752

Filing Date: December 4, 2003

Confirmation No: 2060

Title: METHOD FOR PATTERNING A LOW ACTIVATION ENERGY PHOTORESIST

**AMENDMENT UNDER 37 CFR § 1.111  
AND REQUEST FOR EXTENSION OF TIME**

Mail Stop Amendment  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

This is in response to the Office Action mailed from the PTO on August 10, 2007. A two-month extension of time is requested. The fee for the extension accompanies this response. Please amend the application as indicated herein.

The *Listing of the Claims* begins on page 2 of this document. Amendments to the claims are reflected therein. With this amendment, claim 1 has been amended.

*Remarks* begin on page 12 of this document.